

(FILE 'HOME' ENTERED AT 08:48:51 ON 02 JUN 2003)

FILE 'REGISTRY' ENTERED AT 08:49:17 ON 02 JUN 2003

L1 0 S 2,2-THIODIETHANETHIOL
L2 20 S THIODIETHANETHIOL
L3 15 S TMXDI
L4 7440 S 1-15
L5 17 S DETDA

FILE 'USPATFULL, CAPLUS' ENTERED AT 08:54:40 ON 02 JUN 2003

L6 0 S 3524-66-1/RN AND 2778-41-8/RN AND 75389-89-8/RN
L7 0 S 3524-66-1/RN AND 2778-41-8/RN
L8 0 S 3524-66-1/RN AND 75389-89-8/RN
L9 157 S 3524-66-1/RN
L10 17 S L9 AND (ISOCYANATE OR DIISOCYANATE OR POLYISOCYANATE)
L11 6 S L10 AND (OPTICAL OR LENS)
L12 0 S 2778-41-8/RN AND 75389-89-8/RN
L13 3 S TMXDI AND DETDA AND (OPTICAL OR LENS)

=> d 1-3

L13 ANSWER 1 OF 3 USPATFULL

AN 2003:141093 USPATFULL

TI Impact resistant polyureaurethane and method of preparation

IN Nagpal, Vidhu J., Murrysville, PA, UNITED STATES

McDonald, William H., Cranberry Township, PA, UNITED STATES

Smith, Robert A., Murrysville, PA, UNITED STATES

PI US 2003096935 A1 20030522

AI US 2002-287880 A1 20021105 (10)

PRAI US 2001-332827P 20011116 (60)

DT Utility

FS APPLICATION

LN.CNT 1140

INCL INCLM: 528/044.000

NCL NCLM: 528/044.000

IC [7]

ICM: C08G018-00

L13 ANSWER 2 OF 3 USPATFULL

AN 2003:129997 USPATFULL

TI Light stable one-shot urethane-urea elastomers

IN Markusch, Peter H., McMurray, PA, United States

Cline, Robert L., Paden City, WV, United States

Pantone, Richard S., New Martinsville, WV, United States

Guether, Ralf, Pittsburgh, PA, United States

Sekelik, Thomas L., Carnegie, PA, United States

Haider, Karl W., McKees Rocks, PA, United States

PA Bayer Corporation, Pittsburgh, PA, United States (U.S. corporation)

PI US 6562932 B1 20030513

AI US 2001-976397 20011012 (9)

DT Utility

FS GRANTED

LN.CNT 1079

INCL INCLM: 528/058.000

INCLS: 528/064.000; 528/085.000

NCL NCLM: 528/058.000

NCLS: 528/064.000; 528/085.000

IC [7]
ICM: C08G018-10
EXF 528/58; 528/64; 528/85
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L13 ANSWER 3 OF 3 USPATFULL
AN 2000:131977 USPATFULL
TI Impact resistant polyurethane and method of manufacture thereof
IN Slagel, Edwin C., Avondale, AZ, United States
PA Simula Inc., Phoenix, AZ, United States (U.S. corporation)
PI US 6127505 20001003
AI US 1998-145658 19980902 (9)
RLI Continuation-in-part of Ser. No. US 1996-595262, filed on 1 Feb 1996,
now patented, Pat. No. US 5962617 which is a continuation-in-part of
Ser. No. US 1995-382562, filed on 2 Feb 1995, now abandoned
DT Utility
FS Granted
LN.CNT 575
INCL INCLM: 528/061.000
INCLS: 528/063.000; 528/064.000
NCL NCLM: 528/061.000
NCLS: 528/063.000; 528/064.000
IC [7]
ICM: C08G018-02
EXF 528/61; 528/63; 528/64
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

(FILE 'HOME' ENTERED AT 08:48:51 ON 02 JUN 2003)

FILE 'REGISTRY' ENTERED AT 08:49:17 ON 02 JUN 2003

L1 0 S 2,2-THIODIETHANETHIOL
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FILE 'USPATFULL, CAPLUS' ENTERED AT 08:54:40 ON 02 JUN 2003

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L8 0 S 3524-66-1/RN AND 75389-89-8/RN
L9 157 S 3524-66-1/RN
L10 17 S L9 AND (ISOCYANATE OR DIISOCYANATE OR POLYISOCYANATE)
L11 6 S L10 AND (OPTICAL OR LENS)

=> d 1-6

L11 ANSWER 1 OF 6 USPATFULL

AN 92:92892 USPATFULL
TI Hard transparent resins and process for the production thereof
IN Sasagawa, Katsuyoshi, Kanagawa, Japan
Kanemura, Yoshinobu, Kanagawa, Japan
Imai, Masao, Kanagawa, Japan
Suzuki, Toshiyuki, Kanagawa, Japan
PA Mitsui Toatsu Chemicals, Inc., Tokyo, Japan (non-U.S. corporation)
PI US 5166285 19921124
AI US 1992-835307 19920214 (7)
RLI Division of Ser. No. US 1989-362248, filed on 6 Jun 1989, now patented,
Pat. No. US 5104953
PRAI JP 1988-140484 19880609
DT Utility
FS Granted
LN.CNT 913
INCL INCLM: 526/288.000
INCLS: 526/301.000
NCL NCLM: 526/288.000
NCLS: 526/301.000
IC [5]
ICM: C08F012-30
EXF 526/301; 526/288
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L11 ANSWER 2 OF 6 USPATFULL

AN 92:34245 USPATFULL
TI Radiation-curable liquid resin for secondary coating of lightwave
guides
IN Birkle, Siegfried, Hoechststadt A/Aisch, Germany, Federal Republic of
Feucht, Hans-Dieter, Erlangen, Germany, Federal Republic of
Kamps, Rainer, Coburg, Germany, Federal Republic of
Rissel, Eva, Forchheim, Germany, Federal Republic of
PA Siemens Aktiengesellschaft, Berlin & Munich, Germany, Federal Republic
of (non-U.S. corporation)
PI US 5109089 19920428
AI US 1991-720927 19910625 (7)
RLI Division of Ser. No. US 1988-286472, filed on 19 Dec 1988, now
patented,

Pat. No. US 5057587
PRAI DE 1987-3743993 19871223
DT Utility
FS Granted
LN.CNT 314
INCL INCLM: 526/273.000
INCLS: 525/528.000; 525/530.000; 525/532.000
NCL NCLM: 526/273.000
NCLS: 525/528.000; 525/530.000; 525/532.000
IC [5]
ICM: C08F024-00
EXF 526/273; 525/528; 525/530; 525/532
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L11 ANSWER 3 OF 6 USPATFULL
AN 92:29770 USPATFULL
TI Hard transparent resins and process for the production thereof
IN Sasagawa, Katsuyoshi, Kanagawa, Japan
Kanemura, Yoshinobu, Kanagawa, Japan
Imai, Masao, Kanagawa, Japan
Suzuki, Toshiyuki, Kanagawa, Japan
PA Mitsui Toatsu Chemicals, Inc., Tokyo, Japan (non-U.S. corporation)
PI US 5104953 19920414
AI US 1989-362248 19890606 (7)
PRAI JP 1988-140484 19880609
DT Utility
FS Granted
LN.CNT 917
INCL INCLM: 526/301.000
NCL NCLM: 526/301.000
NCLS: 526/288.000
IC [5]
ICM: C08F026-02
EXF 526/301
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L11 ANSWER 4 OF 6 USPATFULL
AN 91:84530 USPATFULL
TI Radiation-curable liquid resin for secondary coating of lightwave
guides
IN Birkle, Siegfried, Hoechststadt A/Aisch, Germany, Federal Republic of
Feucht, Hans-Dieter, Erlangen, Germany, Federal Republic of
Kamps, Rainer, Coburg, Germany, Federal Republic of
Rissel, Eva, Forchheim, Germany, Federal Republic of
PA Siemens Aktiengesellschaft, Berlin & Munich, Germany, Federal Republic
of (non-U.S. corporation)
PI US 5057587 19911015
AI US 1988-286472 19881216 (7)
PRAI DE 1987-3743993 19871223
DT Utility
FS Granted
LN.CNT 306
INCL INCLM: 526/273.000
NCL NCLM: 526/273.000
IC [5]
ICM: C08F024-00
EXF 560/224; 560/160; 556/457; 526/273
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L11 ANSWER 5 OF 6 USPATFULL
AN 81:16451 USPATFULL
TI Photosensitive resin composition
IN Nagashima, Akira, Shizuoka, Japan
Sato, Shigeru, Odawara, Japan
PA Fuji Photo Film Co., Ltd., Minami-ashigara, Japan (non-U.S.
corporation)

PI US 4258123 19810324
 AI US 1979-70556 19790829 (6)
 PRAI JP 1978-105196 19780829
 DT Utility
 FS Granted
 LN.CNT 723
 INCL INCLM: 430/281.000
 INCLS: 430/283.000; 430/284.000; 430/285.000; 430/286.000; 430/343.000;
 430/344.000; 430/916.000; 430/920.000; 430/925.000; 430/292.000
 NCL NCLM: 430/281.100
 NCLS: 430/283.100; 430/284.100; 430/285.100; 430/286.100; 430/292.000;
 430/343.000; 430/344.000; 430/916.000; 430/920.000; 430/925.000;
 522/016.000; 522/026.000; 522/034.000; 522/121.000
 IC [1]
 ICM: G03C001-68
 EXF 430/916; 430/920; 430/925; 430/343; 430/344; 430/281; 430/283; 430/285;
 430/284; 430/286; 430/292; 430/287; 430/288
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L11 ANSWER 6 OF 6 CAPLUS COPYRIGHT 2003 ACS
 AN 1990:199852 CAPLUS
 DN 112:199852
 TI Hard transparent resins from monomers containing [(isopropenyl-
 .alpha.,.alpha.-dimethylbenzyl)amino]carbonyl groups
 IN Sasagawa, Katsuyoshi; Kanemura, Yoshinobu; Imai, Masao; Suzuki, Toshiyuki
 PA Mitsui Toatsu Chemicals, Inc., Japan
 SO Eur. Pat. Appl., 37 pp.
 CODEN: EPXXDW

DT Patent
 LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 345748	A2	19891213	EP 1989-110275	19890607
	EP 345748	A3	19910515		
	EP 345748	B1	19950426		
	R: CH, DE, FR, GB, IT, LI, NL, SE				
	JP 02084406	A2	19900326	JP 1989-141203	19890605
	JP 2641763	B2	19970820		
	US 5104953	A	19920414	US 1989-362248	19890606
	AU 8936185	A1	19891214	AU 1989-36185	19890608
	AU 605987	B2	19910124		
	BR 8902738	A	19900201	BR 1989-2738	19890609
	CN 1040365	A	19900314	CN 1989-106048	19890609
	CN 1029851	B	19950927		
	US 5166285	A	19921124	US 1992-835307	19920214
	CN 1104648	A	19950705	CN 1994-116091	19940919
	CN 1104649	A	19950705	CN 1994-116092	19940919
	CN 1108667	A	19950920	CN 1994-116093	19940919
	CN 1065525	B	20010509		
PRAI	JP 1988-140484	A	19880609		
	US 1989-362248	A3	19890606		

L Number	Hits	Search Text	DB	Time stamp
1	1396	((528/60) or (528/61) or (528/63) or (528/64)).CCLS.	USPAT	2003/06/02 11:17
2	259	((528/60) or (528/61) or (528/63) or (528/64)).CCLS.) and (thiol or mercap\$)	USPAT	2003/06/02 11:19